



IntelliSense Deep-RIE calibration tool

The Aspect Ratio Dependence of the Etch rate (ARDE) is a normal phenomenon in Deep-RIE, where the rate is often limited by the transport of etching species to the trench bottom and the transport of etch products out of the trenches. It is necessary to accurately predict the relationship between the etching depth and the width of the layout in designs, so that a device meeting the desired performance requirements can be designed and manufactured. Different devices and different conditions make ARDE different because of the complexity of the Deep-RIE process, which affects its reliability and stability. Now, a calibration tool provided by IntelliSense can help customers to calibrate simulation results to their own devices and conditions. IntelliSuite can perform precise process analysis after calibration, and help you to predict accurate etching results in your manufacturing process with ARDE. Indeed, you can design a variety of devices with qualified performance.

